

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Etienne QUESNEL et al.

Application No.: New U.S. Patent Application

Filed: April 5, 2004

Docket No.: 119364

For: PROCESS DESIGNED TO PREVENT DEPOSITION OF CONTAMINATING  
PARTICLES ON THE SURFACE OF A MICRO-COMPONENT, MICRO-COMPONENT  
STORAGE DEVICE AND THIN LAYER DEPOSITION DEVICE

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

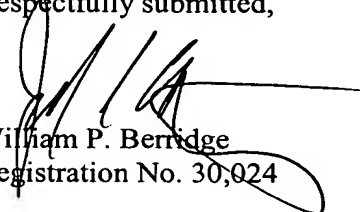
Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- ☒ 2. Relevance of reference No. 4 is discussed in the present specification.
- ☒ 3. The references were cited in a counterpart foreign application. An English language version of the foreign search report is attached for the Examiner's information.
- ☒ 4. The present application was filed or entered the U.S. National Stage of the PCT after June 30, 2003. In accordance with the June 11, 2003, Notice waiving the requirements of 37 CFR §1.98(a)(2)(i), copies of any U.S. patents and patent application publications are not attached.

- ☒ 5. An English-language Abstract of non-English language reference No. 2 is attached hereto.
- ☒ 6. A computer-generated English translation of the following Japanese Patent Publication has been obtained from the website of the Japanese Patent Office ([<http://www.jpo.go.jp>]), and is attached, but has not been reviewed for accuracy. See Reference 2.

Respectfully submitted,



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Date: April 5, 2004

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<p><b>DEPOSIT ACCOUNT USE AUTHORIZATION</b> Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461</p>
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Form PTO-1449 (REV. 8-83)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 119364		APPLICATION NO. New U.S. Patent Application	
INFORMATION DISCLOSURE STATEMENT  (Use several sheets if necessary)				APPLICANTS Etienne QUESNEL et al.			
				FILING DATE April 5, 2004			
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	
	1	4,392,453	7/12/1983	LUSCHER			
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	
	2	JP A 7-291790 w/ Abst & Trans	11/7/1995	Japan			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)							
	3	KOJIMA et al. "IMPURITY GENERATION FOR LOW ENERGY RANGE OF ION BOMBARDMENT AND ITS TRANSPORT IN A PLASMA," Journal of Nuclear Materials 241-243 (1997), pp. 1248-1252.					
	4	WALTON et al. "EXTREME ULTRAVIOLET LITHOGRAPHY - REFLECTIVE MASK TECHNOLOGY," Emerging Lithographic Technologies IV, Proceedings of SPIE Vol. 3997 (2000) pp. 496-507.					
	5	HUE et al. "REDUCTION OF DEFECT DENSITY ON BLANKS: APPLICATION TO THE EXTREME ULTRAVIOLET LITHOGRAPHY," Microelectric Engineering 61-62 (2002), pp. 203-211.					
EXAMINER					DATE CONSIDERED		
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

Date: April 5, 2004